

Docket No.: 300.1160

OK to Enlan

IN THE CN性的 STATES PATENT AND TRADEMARK OFFICE

Group Art Unit: 2812

Examiner: SMITH, BRADLEY

In re the Application of:

N Haruo SORIMACHI

Serial No. 10/828,328

Confirmation No. 4234

Filed: April 21, 2004

For: A METHOD OF PRODUCING VIAS AND OTHER CONDUCTOR PARTS ON AI

ELECTRODE TERMINAL FORMING SURFACE OF A SEMICONDUCTOR

WAFER (As Amended)

AMENDMENT AFTER ALLOWANCE UNDER 37 C.F.R. 1.312

Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

Sir:

Applicants received a Notice of Allowance dated April 19, 2005 in connection with the above-identified application. Please amend the above-identified application as follows, in accordance with the provisions of 37 CFR §1.312 and for the reasons discussed in the accompanying REMARKS.

IN THE TITLE:

Please AMEND the Title as follows:

A METHOD OF PRODUCTION PRODUCING VIAS AND OTHER CONDUCTOR

PARTS ON AN ELECTRODE TERMINAL FORMING SURFACE OF A SEMINCONDUCTOR

DEVICEWAFER.

8/w/06